

# **WAFER HOLDER FOR SEMICONDUCTOR MANUFACTURING DEVICE AND SEMICONDUCTOR MANUFACTURING DEVICE IN WHICH IT IS INSTALLED**

## **Abstract**

Wafer holder for semiconductor manufacturing and semiconductor manufacturing device in which the holder is installed, the wafer holder having a wafer-carrying surface, wherein the isothermal rating of its wafer-carrying surface is enhanced. In the wafer holder having a wafer-carrying surface, by making the diameter  $a$  of the wafer holder wafer-carrying surface not greater than the diameter  $b$  of the surface on its side opposite the wafer-carrying surface, the temperature distribution superficially in a wafer can be brought to within  $\pm 0.5\%$ . Moreover, by making  $b \approx 50 \text{ } \mu\text{m}$ , the temperature distribution can be brought to within  $\pm 0.4\%$ . The wafer holder is preferably a ceramic susceptor.